SILICON PROCESSING FOR THE VLSI ERA

VOLUME 1:

PROCESS TECHNOLOGY

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CONTENTS

PREFACE vii

PROLOGUE xxi

1. SILICON: SINGLE-CRYSTAL GROWTH AND WAFERING 1

- TERMINOLOGY OF CRYSTAL STRUCTURE, 1
- MANUFACTURE OF SINGLE-CRYSTAL SILICON, 5
  From Raw Material to Electronic Grade Polysilicon
- CZOCHRALSKI (CZ) CRYSTAL GROWTH, 8
  Czochralski Crystal Growth Sequence
  Incorporation of Impurities into the Crystal (Normal Freezing)
  Modifications Encountered to Normal Freezing in CZ Growth
  Czochralski Silicon Growing Equipment
  Analysis of Czochralski Silicon in Ingot Form
  Measuring Oxygen and Carbon in Silicon Using Infrared Absorbance Spectroscopy
- FLOAT-ZONE SINGLE-CRYSTAL SILICON, 21
- FROM INGOT TO FINISHED WAFER: SLICING; ETCHING; POLISHING, 23
- SPECIFICATIONS OF SILICON WAFERS FOR VLSI, 26
- TRENDS IN SILICON CRYSTAL GROWTH AND VLSI WAFERS, 30

2. CRYSTALLINE DEFECTS, THERMAL PROCESSING, AND GETTERING 36

- CRYSTALLINE DEFECTS IN SILICON, 37
  Point Defects
  One-Dimensional Defects (Dislocations)
  Area Defects (Stacking Faults)
  Bulk Defects and Precipitation
- INFLUENCE OF DEFECTS ON DEVICE PROPERTIES, 51
  Leakage Currents in pn Junctions
  Collector-Emitter Leakage in Bipolar Transistors
  Minority Carrier Lifetimes
  Gate Oxide Quality
  Threshold Voltage Control
  Wafer Resistance to Warpage

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- CHARACTERIZATION OF CRYSTAL DEFECTS, 55
- THERMAL PROCESSING, 56
  Rapid Thermal Processing (RTP)
- OXYGEN IN SILICON, 59
- GETTERING, 61
  Basic Gettering Pinciples
  Extrinsic Gettering
  Intrinsic Gettering

3. VACUUM TECHNOLOGY FOR VLSI APPLICATIONS 73

- FUNDAMENTAL CONCEPTS OF GASES AND VACUUMS, 73
  Pressure Units
  Pressure Ranges
  Mean Free Path and Gas Flow Regimes
- LANGUAGE OF GAS /SOLID INTERACTIONS, 77
- TERMINOLOGY OF VACUUM PRODUCTION AND PUMPS, 78
- ROUGHING PUMPS, 85
  Oil-Sealed Rotary Mechanical Pumps
  Pump Oils
  Roots Pumps
- HIGH VACUUM PUMPS I: DIFFUSION PUMPS, 89
- HIGH VACUUM PUMPS II: CRYOGENIC PUMPS, 92
- HIGH VACUUM PUMPS III: TURBOMOLECULAR PUMPS, 95
- SPECIFICATION OF VACUUM PUMPS FOR VLSI, 97
- TOTAL PRESSURE MEASUREMENT, 97
- MEASUREMENTS OF PARTIAL PRESSURE: Residual Gas Analyzers, 101
  Operation of Residual Gas Analyzers (RGA)
  RGAs and Non-High Vacuum Applications: Differential Pumping
  Interpretation of RGA Spectra
  RGA Specification List
- HIGH GAS FLOW VACUUM ENVIRONMENTS IN VLSI PROCESSING, 104
  Medium and Low-Vacuum Systems
  Throttled High-Vacuum Systems

4. BASICS OF THIN FILMS 109

- THIN FILM GROWTH, 110
- STRUCTURE OF THIN FILMS, 111
- MECHANICAL PROPERTIES OF THIN FILMS, 113
  Adhesion
  Stress in Thin Films
  Other Mechanical Properties
- ELECTRICAL PROPERTIES OF METALLIC THIN FILMS, 118
  Electrical Transport in Thin Films

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5. SILICON EPITAXIAL FILM GROWTH 124

- FUNDAMENTALS OF EPITAXIAL DEPOSITION, 125
  - *The Grove Epitaxial Model*
  - *Gas Phase Mass Transfer*
  - *Atomistic Model Of Epitaxial Growth*
- CHEMICAL REACTIONS USED IN SILICON EPITAXY, 133
- DOPING OF EPITAXIAL FILMS, 136
  - *Intentional Doping*
  - *Autodoping and Solid-State Diffusion*
- DEFECTS IN EPITAXIAL FILMS, 139
  - *Defects Induced During Epitaxial Deposition and their Nucleation Mechanisms*
  - *Techniques for Reducing Defects in Epitaxial Films*
- PROCESS CONSIDERATIONS FOR EPITAXIAL DEPOSITION, 142
  - *Pattern Shift, Distortion, and Washout*
- EPITAXIAL DEPOSITION EQUIPMENT, 145
- CHARACTERIZATION OF EPITAXIAL FILMS, 147
  - *Optical Inspection of Epitaxial Films*
  - *Electrical Characterization*
  - *Epitaxial Film Thickness Measurements*
  - *Infrared Reflectance Measurement Techniques*
- SILICON ON INSULATORS, 151
  - *Silicon on Sapphire*
  - *Silicon on Other Insulators*
- MOLECULAR BEAM EPITAXY OF SILICON, 156

6. CHEMICAL VAPOR DEPOSITION OF AMORPHOUS AND POLYCRYSTALLINE FILMS 161

- BASIC ASPECTS OF CHEMICAL VAPOR DEPOSITION, 162
- CHEMICAL VAPOR DEPOSITION SYSTEMS, 164
  - *Components of Generic CVD Systems*
  - *Terminology of CVD Reactor Design*
  - *Atmospheric Pressure CVD Reactors*
  - *Low-Pressure CVD Reactors*
  - *Plasma-Enhanced CVD: Physics; Chemistry; and Reactor Configurations*
  - *Photon-Induced CVD Reactors*
- POLYCRYSTALLINE SILICON: PROPERTIES AND CVD DEPOSITION, 175
  - *Properties of Polysilicon Films*
  - *CVD of Polysilicon*
  - *Doping Techniques for Polysilicon*
  - *Oxidation of Polysilicon*
- PROPERTIES AND DEPOSITION OF CVD SiO_2 FILMS, 182
  - *Chemical Reactions for CVD Formation*
  - *Step Coverage of CVD SiO_2*
  - *Undoped CVD SiO_2*

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